

ALIGNMENT APPARATUS, ALIGNMENT METHOD,
EXPOSURE APPARATUS AND EXPOSURE METHOD

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ABSTRACT OF THE DISCLOSURE

An alignment apparatus, comprising a position
detection optical system which detects a position of a
10 mark formed on a street line of a substrate and a focus
detection system which detects deviation between an
irradiated region and a focused surface of the position
detection optical system by irradiating a detection light
on a region of said street line and a different region
15 from a region of said mark at a time and detecting a
reflected light of the detection light.